

# Andrew J Knoll

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/2158090/publications.pdf>

Version: 2024-02-01

9  
papers

167  
citations

1163117  
8  
h-index

1474206  
9  
g-index

9  
all docs

9  
docs citations

9  
times ranked

191  
citing authors

#	ARTICLE	IF	CITATIONS
1	Plasma-surface interaction at atmospheric pressure: A case study of polystyrene etching and surface modification by Ar/O <sub>2</sub> plasma jet. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, 05C315.	2.1	28
2	Polystyrene as a model system to probe the impact of ambient gas chemistry on polymer surface modifications using remote atmospheric pressure plasma under well-controlled conditions. <i>Biointerphases</i> , 2015, 10, 029512.	1.6	25
3	Polymer etching by atmospheric pressure plasma jet and surface microdischarge sources: Activation energy analysis and etching directionality. <i>Plasma Processes and Polymers</i> , 2018, 15, 1700217.	3.0	24
4	Cold Atmospheric Pressure Plasma VUV Interactions With Surfaces: Effect of Local Gas Environment and Source Design. <i>Plasma Processes and Polymers</i> , 2016, 13, 1069-1079.	3.0	22
5	Effect of water vapor on plasma processing at atmospheric pressure: Polymer etching and surface modification by an Ar/H <sub>2</sub> O plasma jet. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	2.1	21
6	Biodeactivation of Lipopolysaccharide Correlates with Surface-Bound NO <sub>3</sub> After Cold Atmospheric Plasma Treatment. <i>Plasma Processes and Polymers</i> , 2016, 13, 410-418.	3.0	19
7	Sensitivity of tumor versus normal cell migration and morphology to cold atmospheric plasma-treated media in varying culture conditions. <i>Plasma Processes and Polymers</i> , 2020, 17, 1900103.	3.0	13
8	A comparative study of biomolecule and polymer surface modifications by a surface microdischarge. <i>European Physical Journal D</i> , 2016, 70, 1.	1.3	12
9	Substrate temperature effect on migration behavior of fluorocarbon film precursors in high-aspect ratio structures. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019, 37, 031802.	1.2	3